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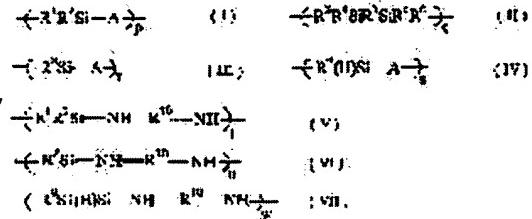
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(54) SILICON-CONTAINING COPOLYMER AND METHOD FOR PRODUCING THE SAME**(57)Abstract:**

PROBLEM TO BE SOLVED: To obtain a polymer having high resistance, high light transmittance, a low dielectric constant, high mechanical strength and flexibility even by curing in air.

SOLUTION: This silicon-containing has 500–1,000,000 number-average molecular weight, contains an Si–O bond and comprises at least structural units represented by general formula (I) and general formula (II) and, if necessary, general formula (III)–(VII) (R1 to R6 and R8 and R9 are each independently an alkyl group, an alkenyl group, a cycloalkyl group, an aryl group, an aralkyl group, an alkylamino group, an alkylsilyl group or an alkoxy group; R7 is a bifunctional group; R10 is a bifunctional aromatic group; A is NH or O).

**LEGAL STATUS**

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